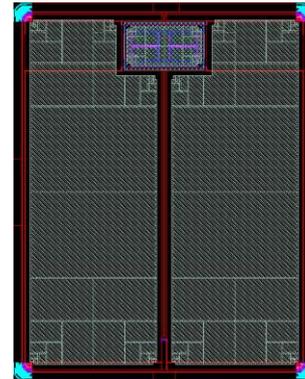


**Description**

Silicon Carbide (SiC) MOSFET use a completely new technology that provide superior switching performance and higher reliability compared to Silicon. In addition, the low ON resistance and compact chip size ensure low capacitance and gate charge. Consequently, system benefits include highest efficiency, faster operating frequency, increased power density, reduced EMI, and reduced system size.

**Features**

- High Speed Switching with Low Capacitances
- High Blocking Voltage with Low RDS(on)
- Simple to drive with Standard Gate Drive
- 100% avalanche tested
- Maximum junction temperature of 175°C
- ROHS Compliant



**Application**

- EV Charging
- DC-AC Inverters
- High Voltage DC/DC Converters
- Switch Mode Power Supplies
- Power Factor Correction Modules
- Motor Drives

Part Number	Die Size
ASC60N1200MB	3.414 × 3.636

**Absolute Maximum Ratings(Tc=25°C)**

Symbol	Parameter	Value	Unit
V <sub>DS</sub>	Drain-Source Voltage	1200	V
I <sub>D</sub>	Drain Current(continuous)at Tc=25°C	60	A
I <sub>D</sub>	Drain Current(continuous)at Tc=100°C	48	A
I <sub>DM</sub>	Drain Current (pulsed)	100	A
V <sub>GS</sub>	Gate-Source Voltage	-10/+22	V
P <sub>D</sub>	Power Dissipation T <sub>c</sub> = 25°C	325	W
T <sub>J</sub> , T <sub>stg</sub>	Junction and Storage Temperature Range	-55 to +150	°C

**Electrical Characteristics(T<sub>J</sub> = 25°C unless otherwise specified)**
**Typical Performance-Static**

Symbol	Parameter	Test Conditions	Min.	Typ.	Max.	Unit
BV <sub>DS</sub>	Drain-source Breakdown Voltage	I <sub>D</sub> =250uA, V <sub>GS</sub> =0V	1200			V
I <sub>DSS</sub>	Zero Gate Voltage Drain Current	V <sub>DS</sub> =1200V, V <sub>GS</sub> =0V, T <sub>J</sub> =25°C			100	uA
I <sub>GSS</sub>	Gate-body Leakage Current	V <sub>DS</sub> =0V ; V <sub>GS</sub> =-10 to 20V			250	nA
V <sub>GS(th)</sub>	Gate Threshold Voltage	V <sub>DS</sub> = V <sub>GS</sub> , I <sub>D</sub> =10mA	2	3	4	V
V <sub>GS(on)</sub>	Recommended turn-on Voltage	Static		20		V
V <sub>GS(off)</sub>	Recommended turn-off Voltage			-5		V
R <sub>DS(on)</sub>	Static Drain-source On Resistance	V <sub>GS</sub> =20V, I <sub>D</sub> =20A		45	52	mΩ
		V <sub>GS</sub> =20V, I <sub>D</sub> =20A T <sub>J</sub> =150°C		72		mΩ

**Typical Performance-Dynamic**

Symbol	Parameter	Test Conditions	Min.	Typ.	Max.	Unit
$C_{iss}$	Input Capacitance	$V_{DS}=1000V, f=100kHz,$ $V_{AC}=25mV$		3239		pF
$C_{oss}$	Output Capacitance			112		pF
$C_{riss}$	Reverse Transfer Capacitance			6		pF
$g_{fs}$	Transconductance	$V_{DS}=20V, I_D=20A$		23		S
$E_{OSS}$	$C_{OSS}$ Stored Energy	$V_{DS}=1000V, f=100kHz$		63		$\mu J$
$E_{ON}$	Turn-On Energy (Body Diode)	$V_{DS}=800V, V_{GS}=-5/20V,$ $I_D=20A, L=100\mu H$ $T_J=150^\circ C$		611		$\mu J$
$E_{OFF}$	Turn-Off Energy (Body Diode)			103		$\mu J$
$Q_g$	Total Gate Charge	$V_{DS}=800V, V_{GS}=-5V/20V,$ $I_D = 20A$		125		nC
$Q_{gs}$	Gate-source Charge			32		nC
$Q_{gd}$	Gate-Drain Charge			33		nC
$R_{G(int)}$	Internal Gate Resistance	$f=1MHz, V_{AC}=25mV$		3.5		$\Omega$
$t_{d(on)}$	Turn-on Delay Time	$V_{DS}=800V, V_{GS}=-5V/20V,$ $I_D = 20A, L=100 \mu H$ $R_{ext}=2.5\Omega$		15		ns
$t_r$	Rise Time			19		ns
$t_{d(off)}$	Turn-off Delay Time			25		ns
$t_f$	Fall Time			10		ns

**Typical Performance-Reverse Diode( $T_J = 25^\circ C$  unless otherwise specified)**

Symbol	Parameter	Test Conditions	Min.	Typ.	Max.	Unit
$V_{FSD}$	Forward Voltage	$V_{GS}=0V, I_F=20A, T_J=25^\circ C$		5	6	V
		$V_{GS}=0V, I_F=20A, T_J=150^\circ C$		4.5	6	V
$I_S$	Continuous Diode Forward Current	$V_{GS}=0V, T_C=25^\circ C$		55		A
$t_{rr}$	Reverse Recovery Time	$V_{GS}=-5V, I_F=20A,$ $V_R=800V, di/dt=900$ $A/\mu s, T_J=150^\circ C$		50		nS
$Q_{rr}$	Reverse Recovery Charge			712		nC
$I_{rrm}$	Peak Reverse Recovery Current			19		A

**Mechanical Parameters**

Parameter	Typical Value	Unit
Die Dimensions(L×W) without scribe line	3.334×3.556	mm
Gate Pad Dimensions(L×W)	0.38×0.55	mm
Source Pad Metal Dimensions (LxW) Each	1.3×3.04×2	mm
Scribe Line	80	um
Die Thickness	175±25	um
Top Side Source metallization (Al)	4	um
Top Side Gate metallization (Al)	4	um
Bottom Drain metallization (Ti/Ni/Ag)	0.2/0.3/2	um

**Chip Dimensions**
